

INTRODUCTION

MF-300 Series developers are surfactant containing developers designed to provide high throughput and wide process latitude for g-line applications in a variety of processes.

FEATURES

- Designed for g-line applications
- Ideal for Microposit S-1800 photoresist series
- Spray and spray/puddle develop processes
- High throughput
- Wide process latitude
- No scumming

Lot-to-lot consistency

Tightly controlled product specifications, Total system functional testing, Statistical process control.

Product Family Comparison

Developer	Normality
Microposit MF-319	0.237
Microposit MF-320	0.255
Microposit MF-321	0.210
Microposit MF-322	0.268

- ✍ MF-319 Developer is designed for high resolution semiconductor devices
- ✍ MF-320 Developer is designed for high resolution semiconductor devices. It should be used in lieu of MF-319 for those who desire a faster photospeed
- ✍ MF-321 Developer provides exceptional resolution and process latitude for high density device fabrication
- ✍ MF-322 Developer provides high photospeed and good processing latitude for high density device fabrication

All Microposit MF-300 series developers can be used in the immersion and batch spray modes, ideal use is in spray and puddle processing on inline track equipment.